

Purge Wafer Stocker

N2-BWS200/800/1600/3200 (Nitrogen purge)



Photo: N2-BWS3200

The area for storing wafers (POD having the purge function) is provided for the wafer sorter. Test wafers and process wafers are contained inside the POD where is kept at low humidity and low oxygen to minimize the change of processed film of wafers.

Features

- 200, 800, 1600 or 3200 wafers storage
- Delivers low oxygen, low humidity, and high level of cleanliness with low nitrogen flow volume
- Automated teaching for aligners and stockers
- The shutter mechanism which opens/closes only the front of the wafer pod minimizes the opening when accessing
- Robot accesses to load ports by interpolation action of VAC adsorption end-effector, which eliminated X-axis

Main specifications

Type	BWS200	BWS800	BWS1600	BWS3200
	RSC151	RI76172	RI76192	RSC2E2
Handling object	300 mm wafer: dia. 300±0.2 mm, Thickness: 775±20 μm			
Carrier	25-slot 300 mm FOUP (SEMI E47.1)			
	25-slot 300 mm FOSB (SEMI M31)			
Power voltage	Single-phase 200 V AC±10% 50/60 Hz±3%	Three-phase 208V AC ±10%, 50/60Hz ±5%		
Current consumption (including FFU)	6 kVA (30 A/200 V AC)	10 kVA (30 A/200 V AC)		25 kVA (75 A/200 V AC)
Vacuum (source pressure)	-90 kPa to -80 kPa			
Vacuum (flow rate)	40 L/min	60 L/min		
Positive pressure (source pressure)	0.6 MPa - 0.7 MPa			
Positive pressure (flow rate)	50 L/min	30 L/min		40 L/min
N2 (source pressure)	0.4 MPa - 0.5 MPa			
N2 (flow rate)	250 L/min	300 L/min	600 L/min	1200 L/min

Option

- Edge clamp
- Chemical filter
- Bar code reader/RF-ID

